

REMARKS

Reconsideration of the subject application is respectfully requested. The title and abstract have been amended to better reflect the current claims. The Examiner's suggestion is appreciated. Claim 21 has also been amended as suggested. Such amendment is intended for clarification purposes but not to narrow the scope of the claim.

Claims 5-9 and 13-17 were rejected under 35 U.S.C. 102(b) as being anticipated by Silverbrook (EP 498 291 A1). This rejection is respectfully traversed. However, in order to expedite prosecution, these claims have been cancelled.

Claims 10-12 and 18-20 were rejected under 35 U.S.C. 103(a) as being unpatentable over Silverbrook in view of Kimura (U.S. 5,389,957). This rejection is respectfully traversed especially in view of the foregoing amendments to independent Claims 10 and 18.

Each of independent Claims 10 and 18 has been amended to recite that the recess has a flat bottom surface and further has been amended to include the subject matter of cancelled Claims 11 and 19, respectively. The bottom of the recess is flat because it is formed by applying wet-anisotropic-etching to the first surface of the silicon substrate, as now specifically recited in each of the independent claims. See Fig. 5(C) and the specification at page 11, lines 6-15, for example. This specifically recited feature saves manufacturing time and still achieves the desired product.

In distinct contrast, Kimura has a contoured recess on orifice plate 400. See Fig. 10 and column 13, lines 14-16, for example. This contoured structure is important to Kimura's device. As stated in column 13, lines 1-13, since the surface is smoothly contoured in the wiping direction, the blade does not vibrate. Thus, Kimura has a distinctly different structure for a distinctly different purpose than that of the present invention, as now specifically recited.

The Examiner's indication of allowability of Claim 21 is appreciated. Claims 12 and 20 depend from Claims 10 and 18, respectively, and are patentable for at least the same reasons as stated above.

In view of the foregoing amendments and remarks, applicants respectfully request favorable reconsideration of the present application.

Respectfully submitted,



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Date: November 18, 2003